

In the Claims

This listing of claims will replace all prior versions, and listings, of claims in the specification:

Listing of Claims

1. (Currently Amended): A manufacturing method of a transfective TFT-LCD panel, comprising the steps of:

A manufacturing method of a transfective TFT-LCD panel, comprising the steps of:

forming a first conductive layer on a substrate;

patterning the first conductive layer to form a gate;

forming a dielectric layer on the substrate to cover the gate;

forming a channel on the dielectric layer and the channel disposed over the gate;

forming a photo-resist block;

forming a second conductive layer to cover the channel and the photo-resist block;

patterning the second conductive layer to form a source, a drain and a ~~photo-reflective layer~~ reflective pixel electrode ~~simultaneously~~, wherein the source and the drain are disposed above the gate, and the ~~photo-reflective layer~~ reflective pixel electrode is formed on the photo-resist block, and the ~~photo-reflective layer~~ reflective pixel electrode and the drain are discrete;

forming a protection layer to cover the source, the drain and the ~~photo-reflective layer~~ reflective pixel electrode;

patterning the protection layer to form a first opening on the drain allowing part of the drain to be exposed, and a second opening on the ~~photo-reflective layer~~ reflective pixel electrode allowing part of the ~~photo-reflective layer~~ reflective pixel electrode to be exposed; and

forming a transparent electrode electrically connected to the drain and the ~~photo-reflective layer~~ reflective pixel electrode via the first opening and the second opening.

2. (Original): A manufacturing method according to claim 1, wherein a capacitor electrode set under the photo-resist block is formed during the step of defining the first conductive layer.

3. (Original): A manufacturing method according to claim 1, wherein the first conductive layer is a first metal layer.

4. (Original): A manufacturing method according to claim 1, wherein the substrate is a glass substrate.

5. (Original): A manufacturing method according to claim 1, wherein the photo-resist block is composed of positive photo-resist.

6. (Original): A manufacturing method according to claim 1, wherein the second conductive layer is a second metal layer.

7. (Original): A manufacturing method according to claim 1, wherein the transparent electrode is composed of indium-tin oxide (ITO).

8. (Currently Amended): A manufacturing method of a transfective TFT-LCD panel equipped with a transmissive area and a reflective area, comprising the steps of:

forming a thin film transistor and a capacitor electrode on the substrate, wherein a ~~photo-reflective layer~~ reflective pixel electrode within the reflective area and a source and a drain of the thin film transistor are formed simultaneously, and the ~~photo-reflective layer~~ reflective pixel electrode and the drain are discrete; and

forming a transparent electrode within the transmissive area to electrically connect the ~~photo-reflective layer~~ reflective pixel electrode and the drain.

9. (Currently Amended): A manufacturing method according to claim 8, wherein the ~~photo-reflective layer~~ reflective pixel electrode is formed substantially above the capacitor electrode.

10. (Currently Amended): A manufacturing method according to claim 8, wherein a photo-resist block is formed on the capacitor electrode prior to the formation of the ~~photo-reflective layer~~ reflective pixel electrode.